

① Device Characteristics:- (JFET)

18/9/14

Consider a symmetrical uniformly doped two-sided depletion mode pn JFET.

→ Aim: Derive I-V characteristics for I_{D1}

Total drain current (in a two-sided device) is $I_{D2} = 2I_{D1}$.

Consider n-channel JFET:

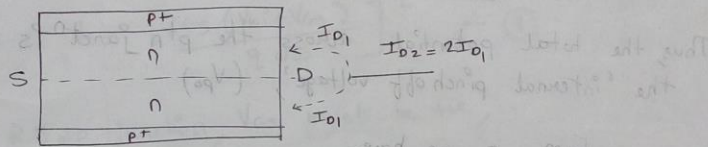
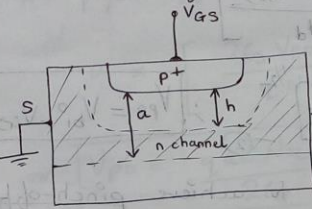


Fig. Drain currents of a symmetrical 2-sided nchannel JFET.

Assume $V_{DS} = 0$.
∴ deplⁿ region width \rightarrow const



Case I:

$V_{DS} = 0$ $h^2 \propto p = \text{const}$

- h - induced depletion region width for one-sided p+n junction
- a - Metallurgical channel thickness betⁿ p+ gate region & the substrate

Extra: Depletion region width for a p-n junction is,

$$W = \sqrt{\frac{2\epsilon_s (V_{bi} + V_r)}{q} \left[\frac{N_a + N_d}{N_a N_d} \right]}$$

For a p+n device $\Rightarrow N_a \gg N_d$

$$W = \sqrt{\frac{2\epsilon_s (V_{bi} + V_r)}{q N_d}}$$

$N_a + N_d \approx N_a$
--- for p+n diode.

② If we assume the abrupt depletion approximation, then the space-charge width is,

$$h = \left[\frac{2\epsilon_s (V_{bi} - V_{GS})}{q N_d} \right]^{1/2} \quad \text{--- (1)}$$

For a rev. bias ptn junction, V_{GS} must be '-ve'.

At pinch-off, $h = a$

Thus, the total potential across the ptn junction is called the 'internal pinch off voltage', (V_{po})

From, a we have

$$a = \left[\frac{2\epsilon_s (V_{bi} - V_{GS})}{q N_d} \right]^{1/2}$$

$$V_{po} = \frac{q a^2 N_d}{2\epsilon_s} \quad \leftarrow \quad a = \left[\frac{2\epsilon_s V_{po}}{q N_d} \right]^{1/2} \quad ; \quad V_{po} = V_{bi} - V_{GS} \quad \text{--- (2)}$$

\rightarrow V_{GS} that must be applied to achieve pinch-off is described as "pinch-off voltage" / "turn-off vty" / "threshold vty". (V_p)

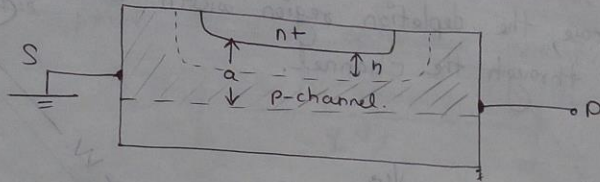
$$\text{From (1) \& (2), } V_{bi} - V_p = V_{po} \Rightarrow V_p = V_{bi} - V_{po} \quad \text{--- (3)}$$

The gate to source voltage to achieve pinch-off in an n-channel JFET is '-ve' - thus $V_{po} > V_{bi}$

* The pinch-off voltage is the gate to source voltage that must be applied to turn the "JFET off".

Similarly, for a p-channel JFET

(3)



Induced depletion region for one-sided n+p junction is

$$h = \left[\frac{2\epsilon_s (V_{bi} + V_{gs})}{q N_a} \right]^{1/2} \quad (3)$$

For a R-B n+p junction, V_{gs} must be +ve,

At pinch-off $h = a$,

$$a = \left[\frac{2\epsilon_s V_{po}}{q N_a} \right]^{1/2}$$

$$\text{or } V_{po} = \frac{q a^2 N_a}{2\epsilon_s} \quad (4)$$

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From (3) and (4), we get

Pinch-off voltage is defined as gate to source voltage to achieve the pinch-off condition, so at pinch-off

$$V_{bi} + V_p = V_{po} \quad \text{or } V_p = V_{po} - V_{bi}$$

⇒ Thus, we have determined the pinch-off voltage for both n-channel and p-channel JFETs when the $V_{gs} = 0$

Case ②: Both V_{gs} and V_{ds} applied.

→ In this case, the depletion region width will vary with the distance through the channel.

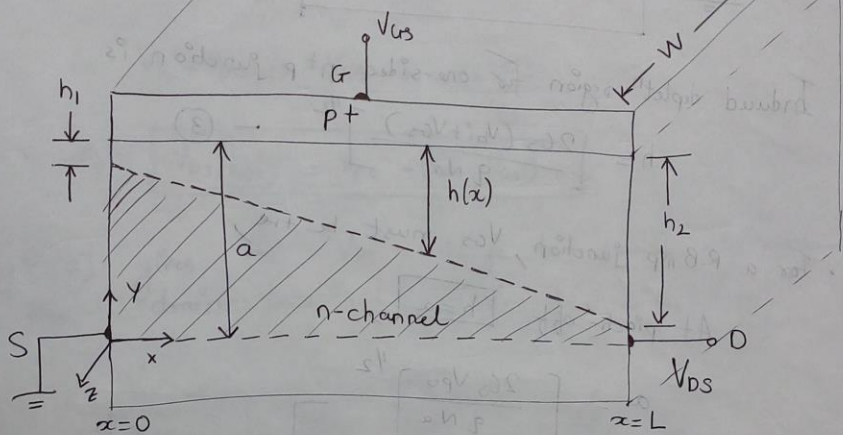


Fig 1 Simplified geometry of an n-channel pn junction FET.

• Depletion width at source end = h_1 → is a function of V_{bi} and V_{gs} .

• Depletion width at drain end = h_2 → is a function of V_{ds} , V_{gs} and V_{bi} .

$$h_2 = \left[\frac{2 \epsilon_s (V_{bi} + V_{ds} - V_{gs})}{q N_d} \right]^{1/2} \quad \text{--- (5)}$$

+ V_{gs} → " V_{gs} , '+ve' applied" ; - V_{gs} → " V_{gs} , '-ve' applied."

Pinchoff at the drain terminal occurs when $h_2 = a$ (5)

→ At this point, we reach saturation condition, i.e. $V_{DS} = V_{DS(sat)}$

$$\Rightarrow a = \left[\frac{2\epsilon_s (V_{bi} + V_{DS(sat)}) - V_{GS}}{qN_d} \right]^{1/2} \quad (6)$$

$$\text{i.e. } V_{bi} + V_{DS(sat)} - V_{GS} = \frac{q a^2 N_d}{2\epsilon_s} = V_{PO}$$

$$\text{i.e. } \boxed{V_{DS(sat)} = V_{PO} - (V_{bi} - V_{GS})} \quad (7)$$

Eqⁿ (7) gives the V_{DS} voltage to cause pinchoff at the drain terminal. (V_{DS} ↓ as V_{GS} ↑sing. Rev bias V_{GS})

$$\text{i.e. } V_{DS(sat)} = V_{GS} - (V_{bi} - V_{PO})$$
$$\boxed{V_{DS(sat)} = V_{GS} - V_P} \quad (8) \text{ from (a)}$$

Similarly, in a p-channel JFET, at saturation,

$$\boxed{V_{SD(sat)} = V_{PO} - (V_{bi} + V_{GS})}$$

where, now source is +ve w.r.t the drain.

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— X —

* "Ideal dc I-V Relationship" (5)

Depletion mode n-channel JFET

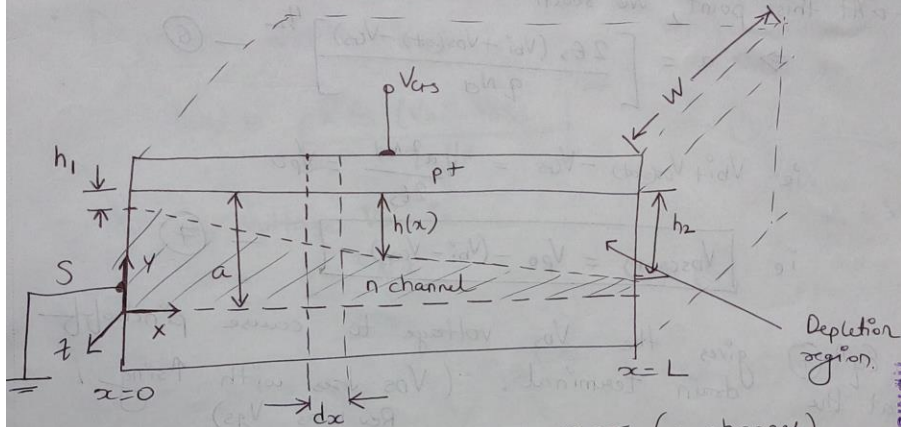


fig (1a): Structure of JFET (n-channel).

Consider a differential incremental strip of length 'dx' across the channel.

(We are moving this strip from S to D, such that it covers the total current).

Differential volume in the channel = $W [a - h(x)] dx$ — (1)

Resistance of the differential volume = $\frac{\rho \cdot d}{A} \approx \frac{\rho dx}{W [a - h(x)]}$ — (2)

Conductivity (σ) = $\frac{W [a - h(x)]}{\rho dx}$. $\sigma = \frac{1}{R}$ → resistance.

$$I_D = \frac{w [a - h(x)]}{s} dV_x \quad (3)$$

(Considering differential voltage change as dV_x)

• Depletion width $h(x)$ is

$$h(x) = \left[\frac{2\epsilon_s (V_{bi} - V_{Gx})}{q N_d} \right]^{1/2} \quad (4)$$

• Pinch-off voltage V_p is

$$V_p = \frac{q a^2 N_d}{2\epsilon_s} \quad (5)$$

V_{Gx}
→ gate to 'x'
distance
voltage.

ie $h(x) = a \left(\frac{V_{bi} - V_{Gx}}{V_p} \right)^{1/2}$ (From (4) & (5),

$$a - h(x) = a \left[1 - \left(\frac{V_{bi} - V_{Gx}}{V_p} \right)^{1/2} \right]$$

$$a - h(x) = a \left[1 - \left(\frac{V_{bi} - V_G + V_x}{V_p} \right)^{1/2} \right] \quad (6)$$

From (3) and (6), we get

$$I_D dx = \frac{W a}{s} \left[1 - \left(\frac{V_{bi} - V_G + V_x}{V_p} \right)^{1/2} \right] dV_x$$

Total drain current I_D from $x=0$ to $x=L$
 \equiv (V_x will change from 0 to V_0)

$$\text{i.e. } \int_0^L I_D dx = \frac{W_a}{g} \int_0^{V_D} \left[1 - \left(\frac{V_{bi} + V_x - V_G}{V_p} \right)^{1/2} \right] dV_x \quad (6)$$

$$\text{i.e. } I_D \cdot L = \frac{W_a}{g} \left[V_x - \frac{2}{3V_p^{1/2}} (V_{bi} + V_x - V_G)^{3/2} \right]_0^{V_D}$$

$$I_D = \frac{W_a}{gL} \left[V_D - \frac{2}{3V_p^{1/2}} (V_{bi} + V_D - V_G)^{3/2} - \left\{ 0 - \frac{2}{3V_p^{1/2}} (V_{bi} - V_G + 0)^{3/2} \right\} \right]$$

$$I_D = \frac{W_a}{gL} \left[V_D - \frac{2}{3V_p^{1/2}} (V_{bi} - V_G + V_D)^{3/2} + \frac{2}{3V_p^{1/2}} (V_{bi} - V_G)^{3/2} \right] \quad (7)$$

* In linear region, $V_D \ll V_G$ and $V_D \ll V_{bi}$, so (by binomial series expansion)

$$I_{D \text{ linear}} \approx \frac{W_a}{gL} \left[1 - \left(\frac{V_{bi} - V_G}{V_p} \right) \right] V_D$$

$$I_{D \text{ linear}} \approx G \left[1 - \left(\frac{V_{bi} - V_G}{V_p} \right) \right] V_D \quad (8)$$

where, $G = \frac{W_a}{gL} \rightarrow$ is the channel conductance.

In saturation region,

$$V_D = V_{Dsat} = V_p + V_G - V_{bi} = V_G - (V_{bi} - V_p)$$

$$= V_G - V_T$$

gate threshold voltage.

From eqn (7), saturation current is,

$$I_{Dsat} = G \left[(V_p - V_{bi} + V_G) - \frac{2}{3V_p^{1/2}} (V_{bi} - V_G + V_p - V_{bi} + V_G)^{3/2} + \frac{2}{3V_p^{1/2}} (V_{bi} - V_G)^{3/2} \right]$$

$$= G \left[V_p - (V_{bi} - V_G) - \frac{2}{3} V_p^{(1/2 - 1/2)} + \frac{2}{3V_p^{1/2}} (V_{bi} - V_G)^{3/2} \right]$$

$$= G \left[V_p - (V_{bi} - V_G) - \frac{2}{3} V_p + \frac{2}{3} (V_{bi} - V_G)^{3/2} \frac{1}{V_p^{1/2}} \right]$$

$$I_{Dsat} = G V_p \left[\frac{1}{3} - \frac{V_{bi} - V_G}{V_p} + \frac{2}{3} \left[\frac{(V_{bi} - V_G)}{V_p} \right]^{3/2} \right]$$

(9)

Extra! For $V_D \gg V_{Dsat}$, the pinch-off starts shifting towards source. While there is a shift in the pinch-off point, potential at pinch-off points will remain constant at V_{Dsat} , so Electric field in drain region remain constant and current I_D thus saturates.

Experimentally it has been found that

$$I_{Dsat} = I_{DSS} \left[1 - \frac{V_{GS}}{V_P} \right]^2 \quad (10)$$

where I_{DSS} is the saturation drain current at $V_{GS} = 0 \Rightarrow$ & is given by,

$$I_{DSS} = \frac{\mu_n C_{ox} W V_P}{3SL}$$

* Transconductance (g_m):

It is the transistor gain of a JFET. It indicates the amount of control the gate has on drain current.

$$g_m = \frac{\partial I_{Dsat}}{\partial V_{GS}} \quad \text{Experimental transconductance.}$$

From eqⁿ (10), we can write

$$g_{msat} = -\frac{2}{V_P} I_{DSS} \left(1 - \frac{V_{GS}}{V_P} \right) \quad (11)$$

Since, V_P is 've' for n-channel JFET,

g_{msat} will be +ve.

$$* g_{msat \max} \approx \frac{3I_{DSS}}{V_{P0}} \left[1 - \sqrt{\frac{V_{bi}}{V_{P0}}} \right]$$